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Doping Techniques in Emerging Semiconductors and Devices

Guest Editor:

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Message from the Guest Editor

Dear Colleagues,

Over the past decade, emerging thin-film semiconductors such as transition-metal dichalcogenides (TMDs), carbon nanotubes, oxides, and organic materials have been intensively investigated as next-generation semiconducting materials, owing to their excellent electrical, chemical, mechanical, and optical properties. However, conventional doping techniques, such as ion-implantation, damage these thin-film materials, and there is a great need to develop an alternative method to control the electrical properties.

This Special Issue calls for research papers, reviews, and short communications related to state-of-the-art developments that contribute to novel doping techniques for high-performance device applications.









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Editor-in-Chief

Message from the Editor-in-Chief

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